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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/814,270	04/01/2004	Yoshinori Okumura	250738US2CONT	8477
22850	7590 10/05/2004		EXAMINER	
OBLON, SPIVAK, MCCLELLAND, MAIER & NEUSTADT, P.C.			PHAM, THANHHA S	
1940 DUKE S ALEXANDR	STREET IA, VA 22314		ART UNIT PAPER NUMBER	
			2813	
			DATE MAILED: 10/05/200	4

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)	
	10/814,270	OKUMURA ET AL.	
Office Action Summary	Examiner	Art Unit	
	Thanhha Pham	2813	
The MAILING DATE of this communication Period for Reply	appears on the cover sheet wi	th the correspondence address -	-
A SHORTENED STATUTORY PERIOD FOR RETHE MAILING DATE OF THIS COMMUNICATIO - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a - If NO period for reply is specified above, the maximum statutory per - Failure to reply within the set or extended period for reply will, by state Any reply received by the Office later than three months after the material patent term adjustment. See 37 CFR 1.704(b).	N. 1.136(a). In no event, however, may a r reply within the statutory minimum of thin iod will apply and will expire SIX (6) MON tute, cause the application to become AB	eply be timely filed y (30) days will be considered timely. THS from the mailing date of this communica ANDONED (35 U.S.C. § 133).	ution.
Status		,	•
1) Responsive to communication(s) filed on 0	1 April 2004.		
	his action is non-final.		
3) Since this application is in condition for allocal closed in accordance with the practice under the condition of the co	•	• •	s is
Disposition of Claims			
4) Claim(s) 1 and 2 is/are pending in the application Papers 4) Claim(s) 1 and 2 is/are pending in the application Papers 4) Claim(s) 1 and 2 is/are rejected. 7) Claim(s) 1 and 2 is/are rejected. 7) Claim(s) 1 and 2 is/are objected to. 8) Claim(s) are subject to restriction and application Papers 9) The specification is objected to by the Exameration The drawing(s) filed on 01 April 2004 is/are:	drawn from consideration. d/or election requirement.	cted to by the Examiner.	
Applicant may not request that any objection to a Replacement drawing sheet(s) including the corn 11) The oath or declaration is objected to by the	the drawing(s) be held in abeyar rection is required if the drawing	ce. See 37 CFR 1.85(a). s) is objected to. See 37 CFR 1.12	
	Examiner. Note the attached	TO THOSE ACTION OF TO HAT TO THE	•
Priority under 35 U.S.C. § 119 12) Acknowledgment is made of a claim for fore a) All b) Some * c) None of: 1. Certified copies of the priority docum 2. Certified copies of the priority docum 3. Copies of the certified copies of the papplication from the International Bur	ents have been received. ents have been received in A priority documents have been	pplication No	
* See the attached detailed Office action for a		received.	
Attachment(s) Notice of References Cited (PTO-892)	∧ □	ummanı (DTO 442)	
 Notice of References Cited (PTO-592) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/Paper No(s)/Mail Date <u>04/01/04</u>. 	Paper No(ummary (PTO-413) s)/Mail Date Iformal Patent Application (PTO-152) 	

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DETAILED ACTION

This Office Action is in response to Applicant's Preliminary Amendment dated 04/01/04.

Oath/Declaration

Oath/Declaration filed on 04/01/04 has been considered.

Claim Objections

1. Claim 1 objected to because of informalities. Appropriate correction is required to clarify the scope of the claim.

Claim 1,

line 11, "layers of insulating films" should be changed to "insulating film" line 12, "an insulating film" should be changed to "insulating film"

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

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2. Claims 1-2 are rejected under 35 U.S.C. 102(e) as being anticipated by Wu et al. [US 6,730,556].

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➤ With respect to claim 1, Wu et al. (fig. 2g, cols. 4-8) discloses a semiconductor device, comprising:

a semiconductor substrate (62) (see col. 4, lines 27-29);

a first transistor (64) which includes a first gate electrode (84) which is formed on said semiconductor substrate (62) (see col. 4, lines 31-37), a first sidewall insulating film (88, 120) (see col. 4, lines 54-58 and col. 6, lines 33-54) which is formed on a side of said first gate electrode (84) on said semiconductor substrate (62) and first source/drain active layers (92) (see col. 7, lines 21-25) which are formed in said semiconductor substrate (62); and

a second transistor (66) which includes a second gate electrode (104) (see col. 4, lines 37-40) which is formed on said semiconductor substrate (62), a second sidewall insulating film (120, 122', 128) (see col. 6, lines 33-54) which is formed on a side of said second gate electrode (104) on said semiconductor substrate (62) and second source/drain active layers (132) (see col. 7, lines 21-25) which are formed in said semiconductor substrate (62), wherein

layers of insulating film which compose said second sidewall insulating film (120, 122', 128) are more in number than layers of insulating film which compose said first sidewall insulating film (88, 120), and accordingly, a width of said second sidewall insulating film (120, 122', 128) in a channel direction of said second transistor (66) is

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larger than a width of said first sidewall insulating film (88, 120) in a channel direction of said first transistor (64) (see fig. 2g).

With respect to claim 2, Wu et al. discloses that the first sidewall insulating film includes a silicon nitride film (120) (see col. 4, lines 54-56), and said second sidewall insulating film (120, 122', 128) (see col. 4, lines 54-60 and col. 6, lines 33-39) includes a silicon nitride film and a silicon oxide film.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thanhha Pham whose telephone number is (571) 272-1696. The examiner can normally be reached on Monday and Thursday 9:00AM - 9:30PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead can be reached on (571) 272-1702. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Thanhha Pham Patent Examiner

Patent Examining Group 2800